Powerful, simple, efficient

AERES

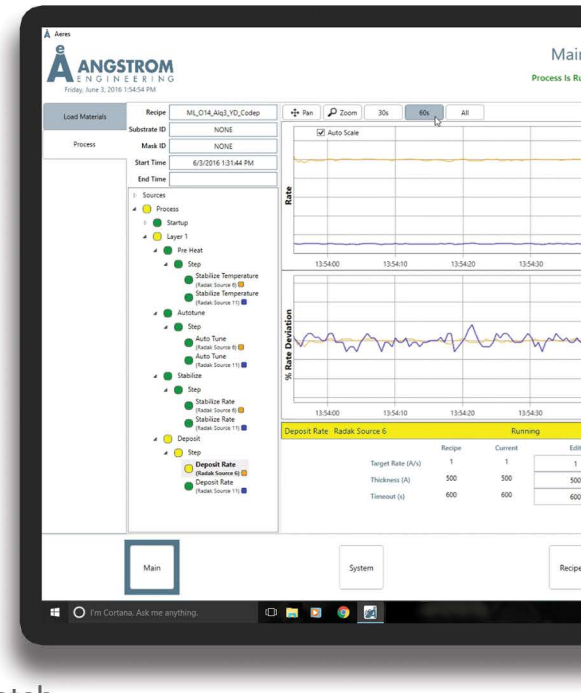
Advanced Process Control Software

ANGSTROM ENGINEERING

Your Thin Film Partner

Advanced Process C

Powerful enough for the
Simple enough for eve



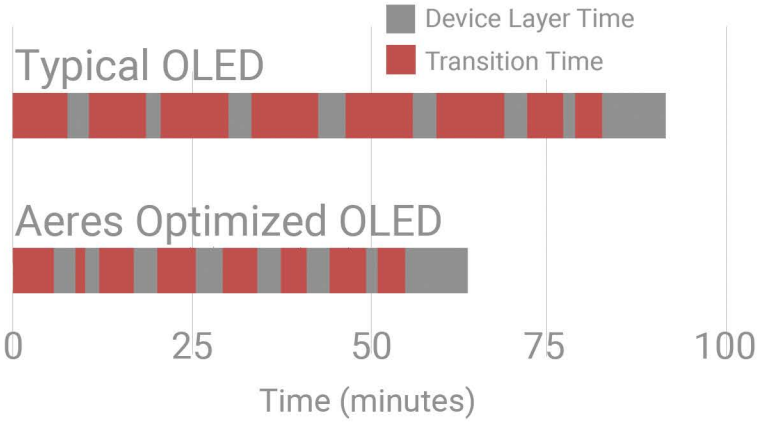
Recipe Control

Every aspect of your process; One unified recipe

Pre-deposition | wafer prep, source ramp-up, & stabilization
Layer control | thickness, rate, shuttering, & source idling
Stage control | heating, cooling, rotation, angle, & biasing
Gas & pressure | pressure stability & precise gas delivery
Automation | press start & leave the system to do **everything**

Create processes as simple or as complex as desired
Use the pre-loaded templates, or build custom sequences from scratch
Build recipes from a remote PC, then seamlessly transfer the recipe over to the deposition tool PC for use
Can run entirely autonomously, or you can build manual control into recipes if desired
The unified data management system collects & logs all pertinent process information

Layer Transition Efficiency



45% reduction in layer transition time
30% improvement in total device fabrication time

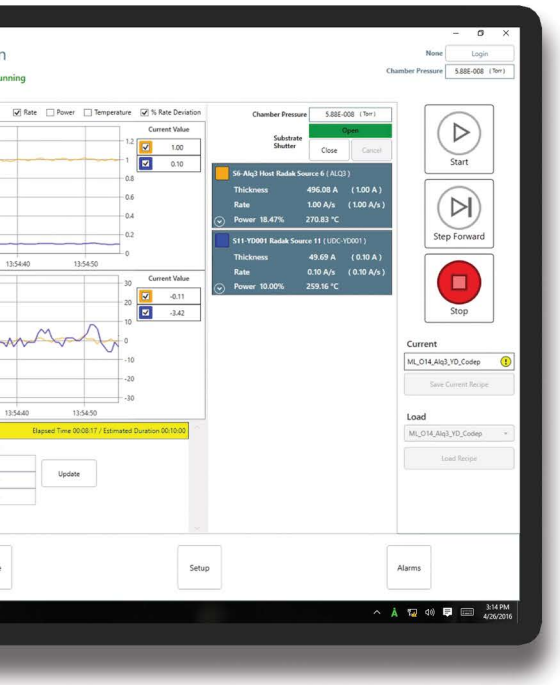
Total device time is dramatically reduced due to **parallel task management**

Parallel task management is the automatic and simultaneous control of background processing. It includes source preparation, mask & sample transferring, power & temperature ramping, & stage preparation, which greatly reduces transition times between layers.

Control Software

most advanced user.

ery user in the lab.



Features

Modern User-Interface

Built on .NET framework and is SECS/GEM ready

Runs on Windows® PC, and is touch-screen compatible

Enabled for multiple-user profiles with administrator control

Complete & thoroughly tested safety & interlock system

Multi-Chamber Capable

Single terminal can control multiple chambers, each with unique recipes

Process control hardware integration

QCM monitoring and control

End point detection using reflection/transmission or ellipsometry

In situ plasma monitoring

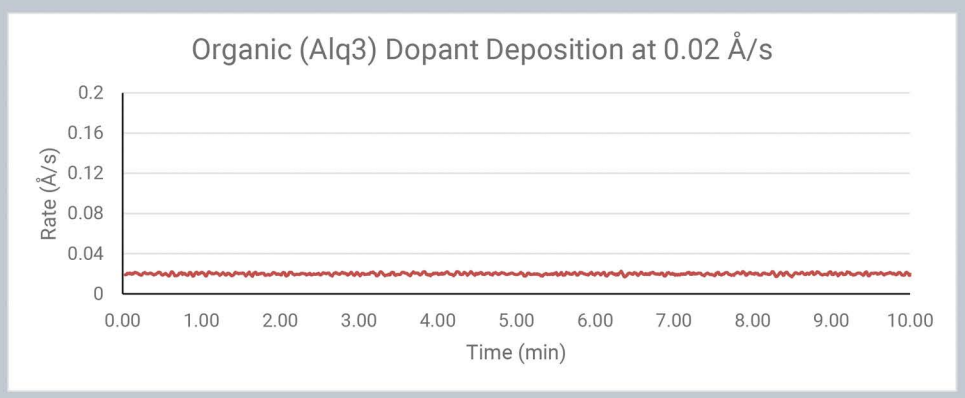
The Angstrom team will provide process support, training, and troubleshooting remotely, or in-person

Advanced Deposition Control

Aeres allows our partners to achieve unprecedented low-rate stability

User adjustable PID detection algorithm (advanced auto-tuning)

Significantly reduce your process development time



Actual stability while depositing a common OLED material (Alq3) at 0.02 Å/s

Aeres and all of its features available across our deposition platforms

Service and Support: Our Commitment

An Angstrom system in your lab makes us partners; we become part of your team. We guarantee **same day** response to any service inquiry regarding parts, technical support, and software support.

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